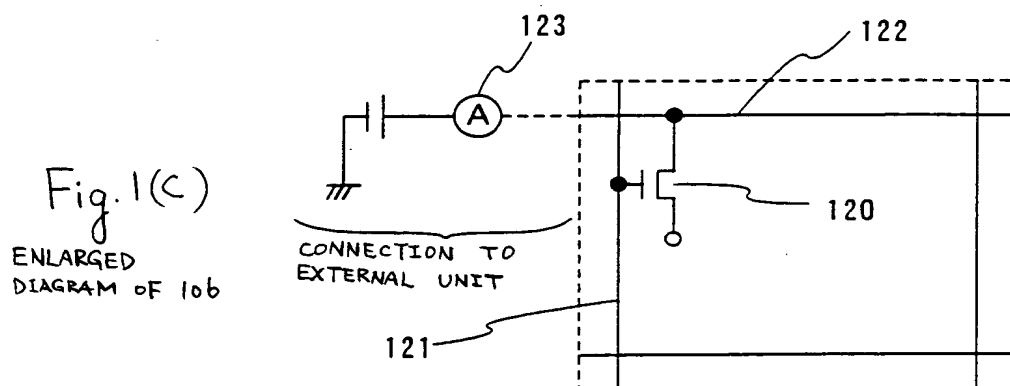
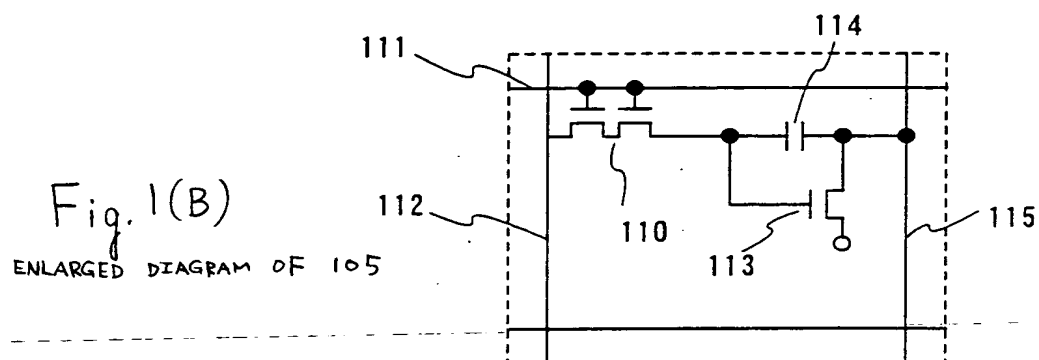
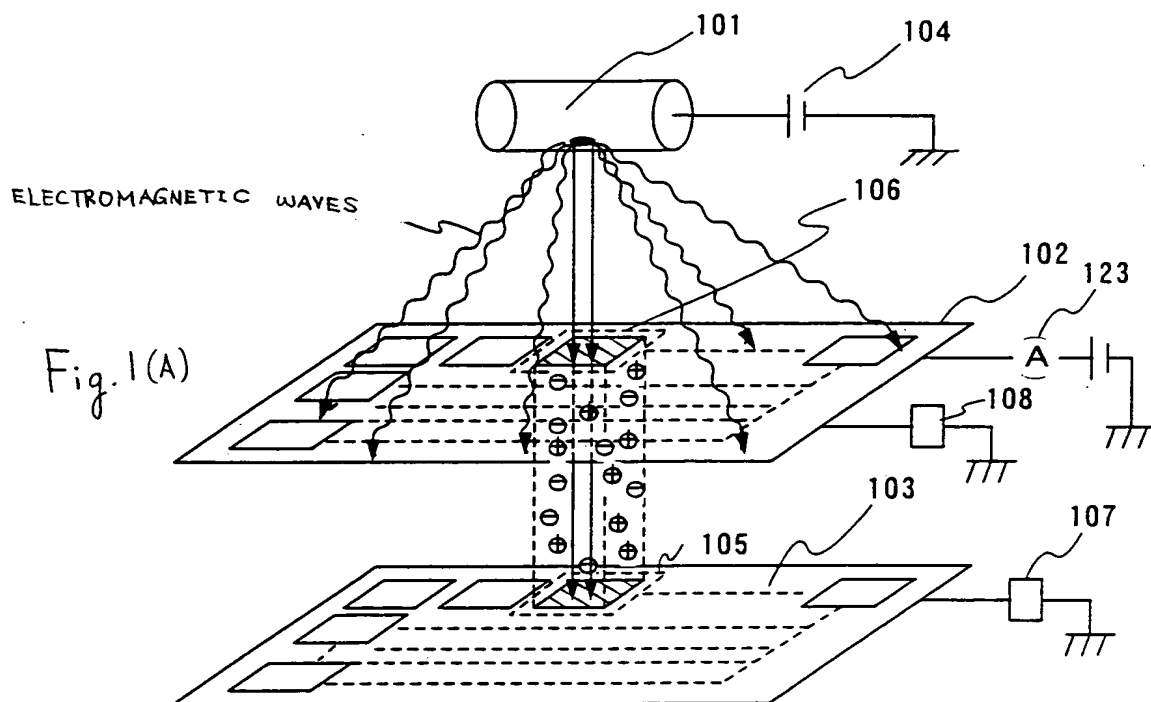


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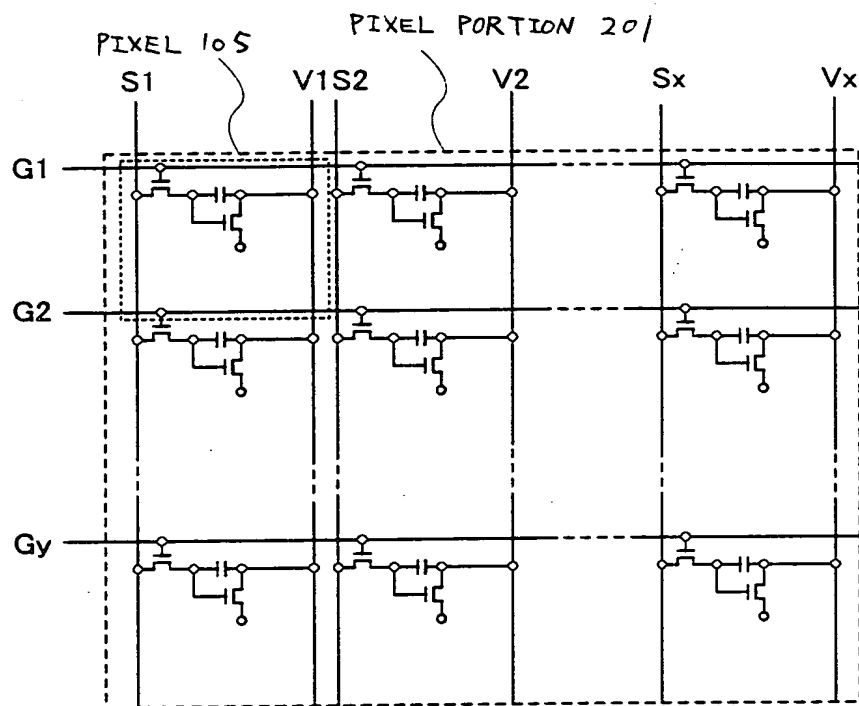


Fig. 2(A)

OPPOSING PORTION 106

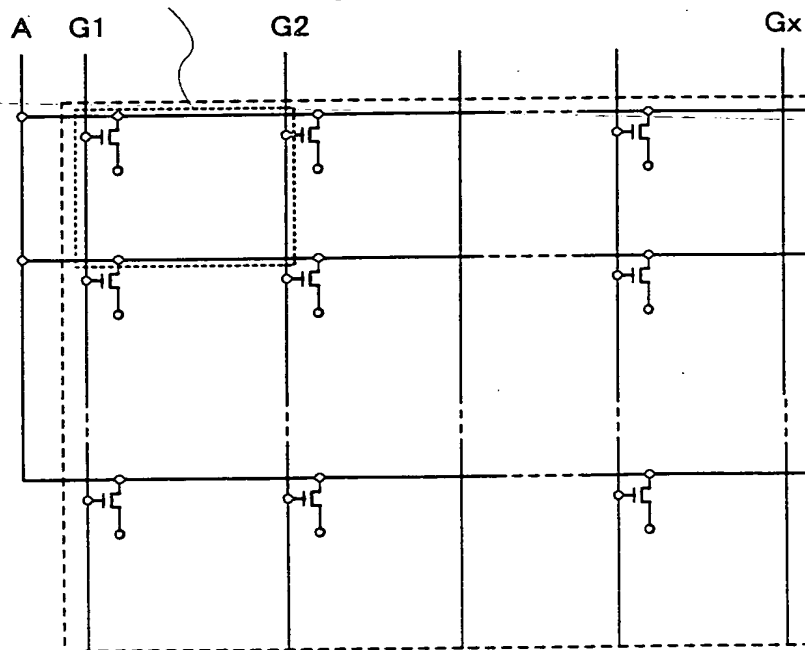


Fig. 2(B)

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Fig. 3(A)

(1, 1)	(2, 1)	(3, 1)	(4, 1)		(x-1, 1)	(x, 1)
(1, 2)	(2, 2)	(3, 2)	(4, 2)		(x-1, 2)	(x, 2)
(1, 3)	(2, 3)	(3, 3)	(4, 3)		(x-1, 3)	(x, 3)
(1, 4)	(2, 4)	(3, 4)	(4, 4)		(x-1, 4)	(x, 4)
(1, y-1)	(2, y-1)	(3, y-1)	(4, y-1)		(x-1, y-1)	(x, y-1)
(1, y)	(2, y)	(3, y)	(4, y)		(x-1, y)	(x, y)

Fig. 3(B)

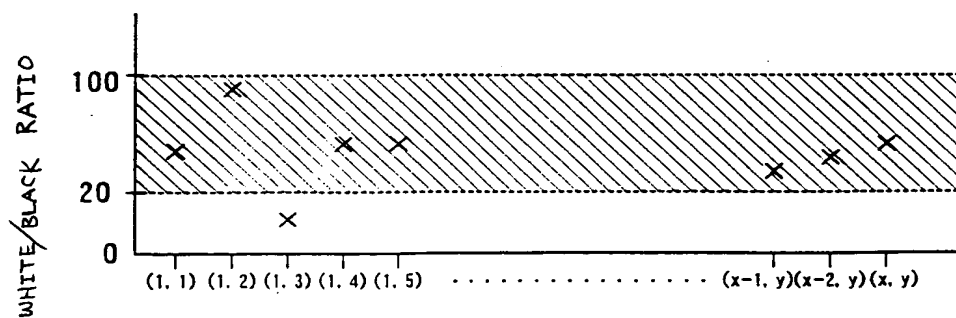




Fig. 5(A) SECOND DOPING

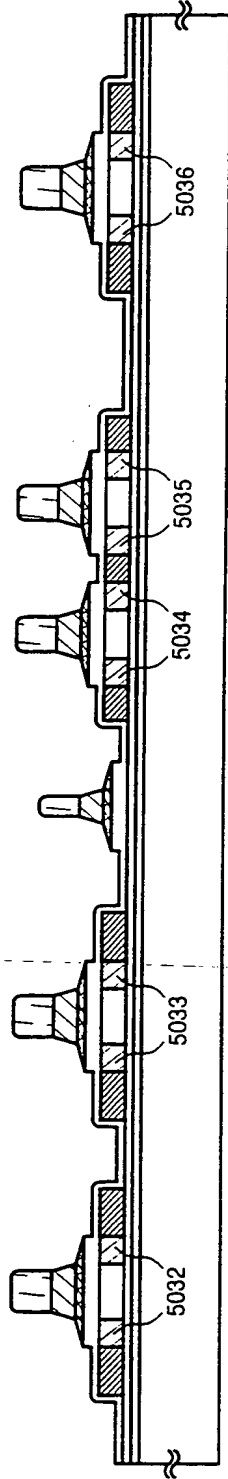


Fig. 5(B) THIRD ETCHING

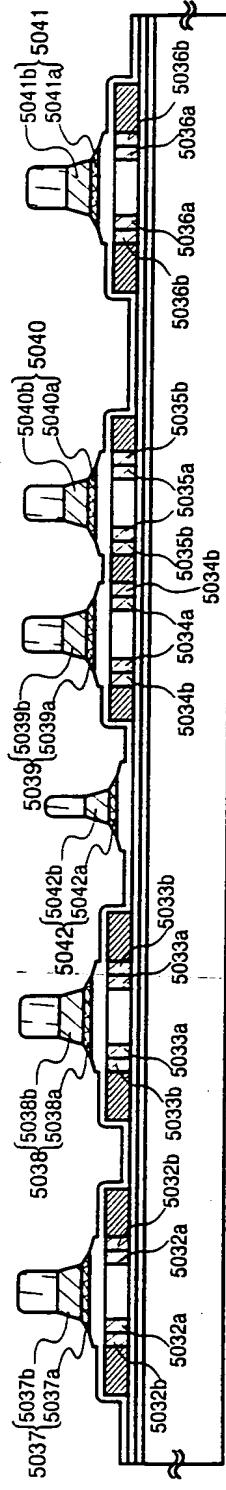
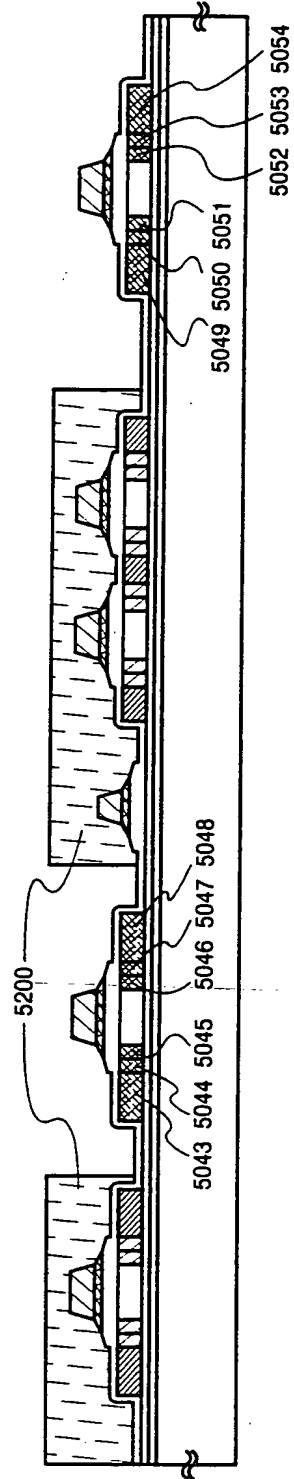
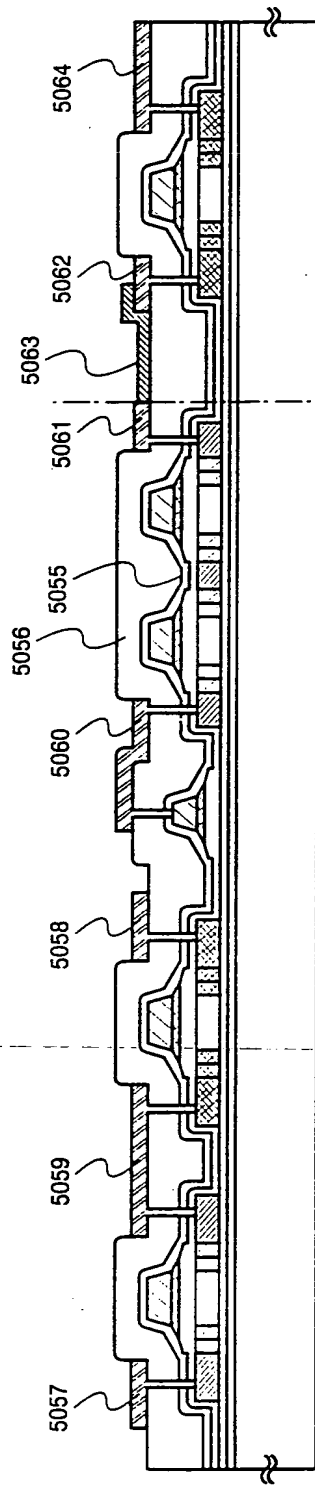


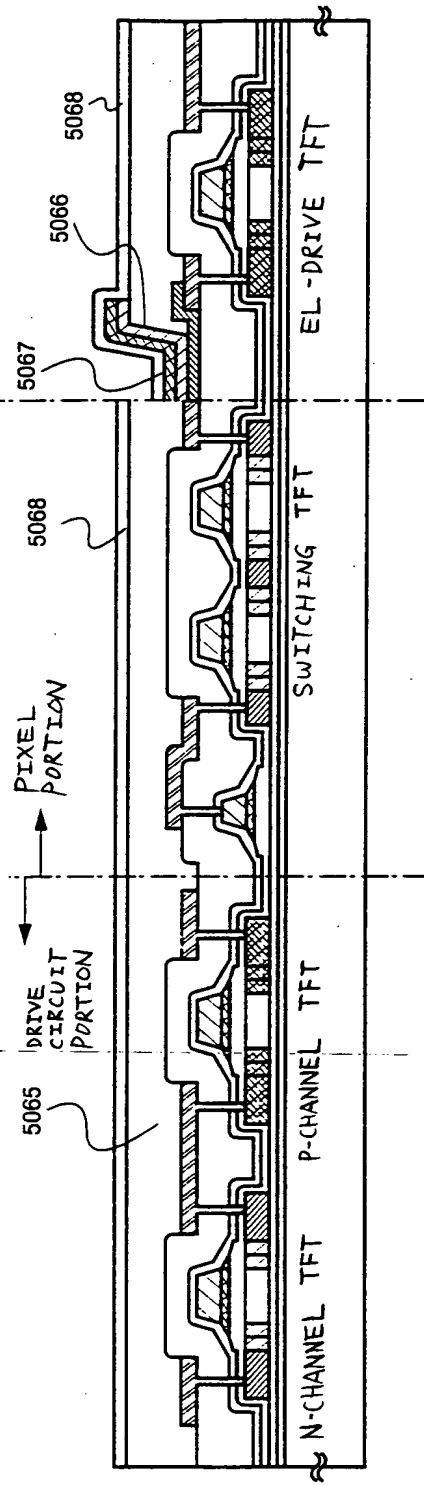
Fig. 5(c) THIRD DOPING

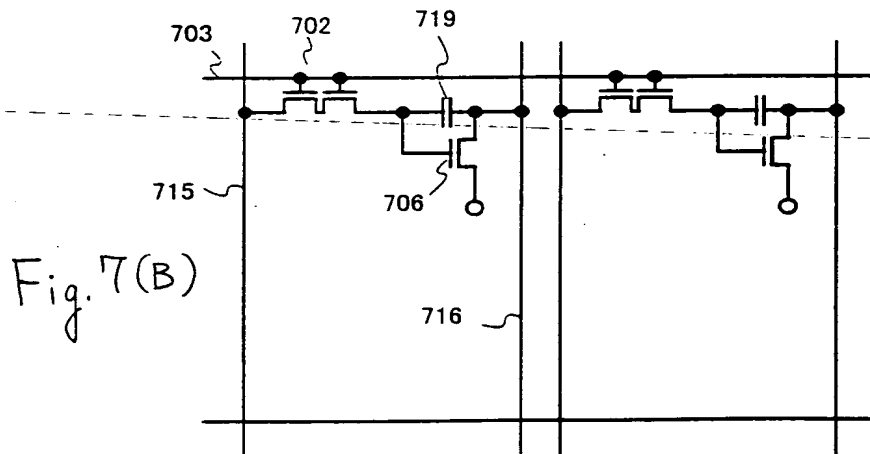
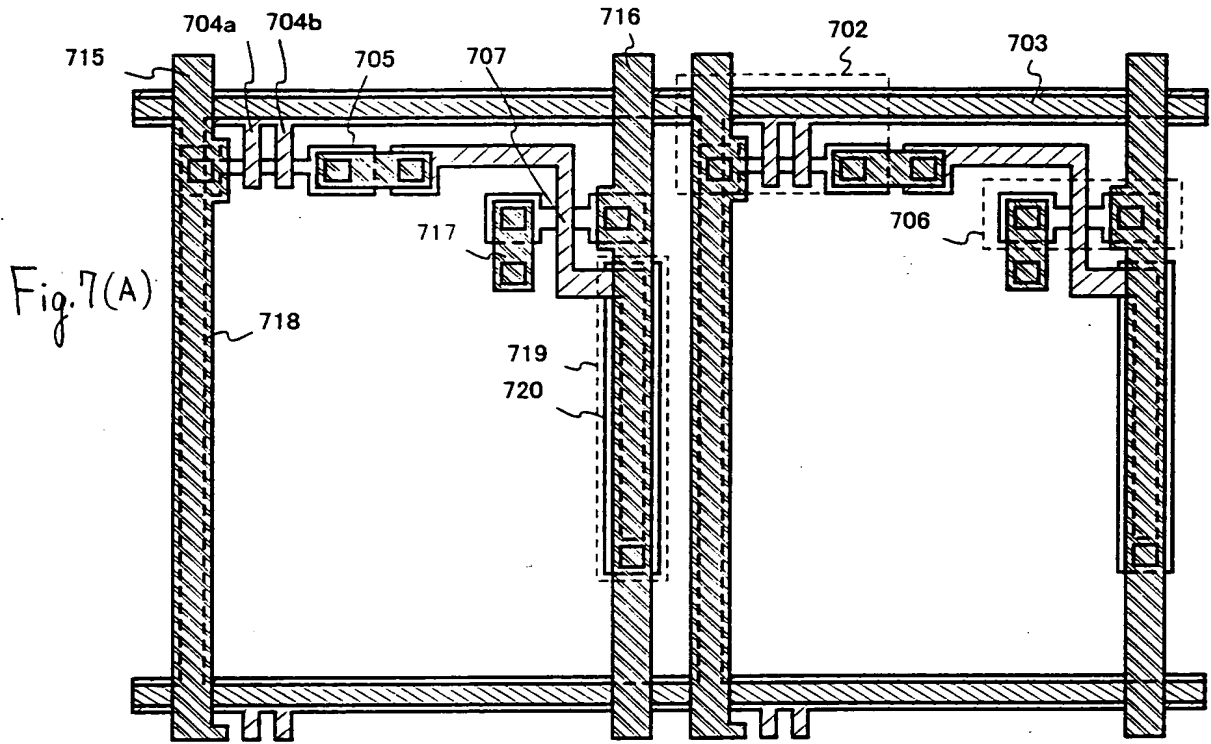


FORMATION OF THE FIRST AND SECOND INTERLAYER-INSULATING FILMS,  
Fig. 6(A) WIRINGS AND PIXEL ELECTRODES

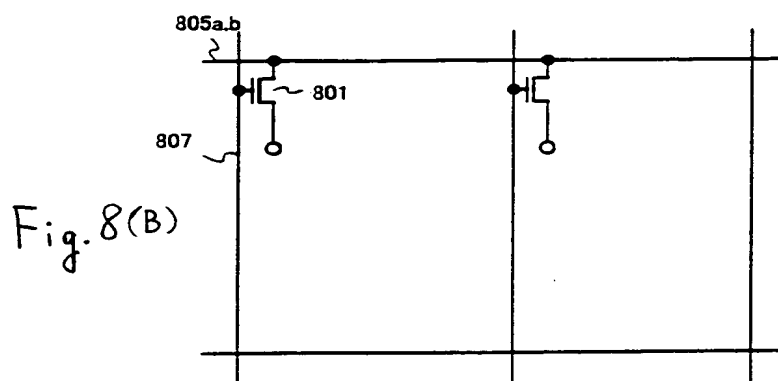
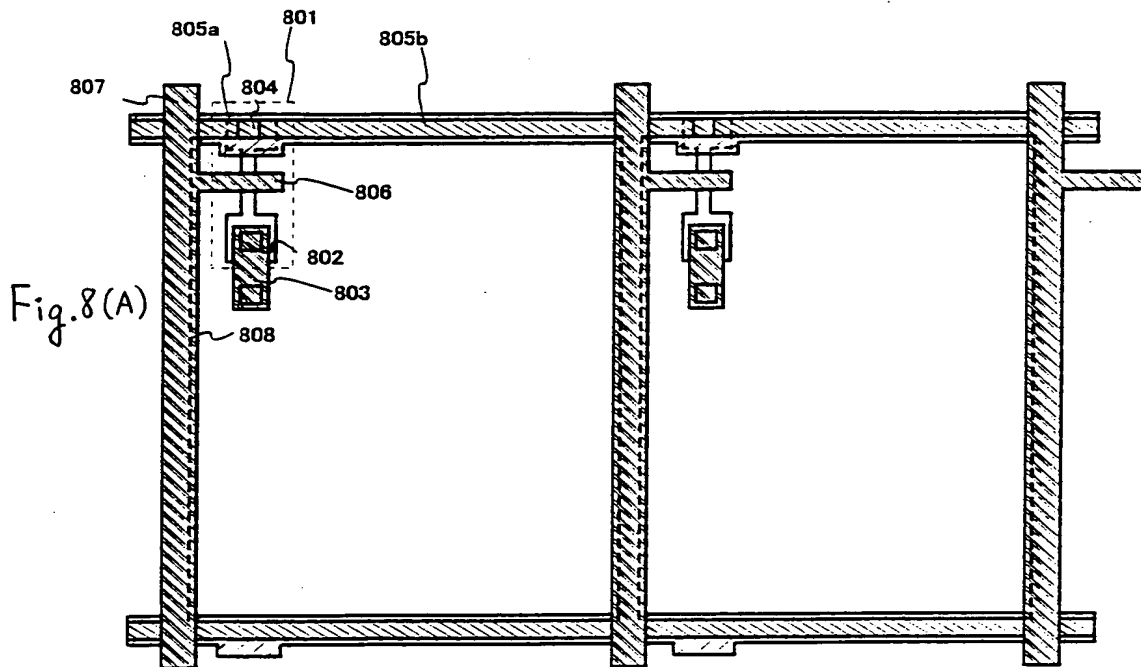


FORMATION OF THE THIRD INTERLAYER-INSULATING FILM, EL LAYER,  
Fig. 6(B) CATHODES AND PASSIVATION FILM





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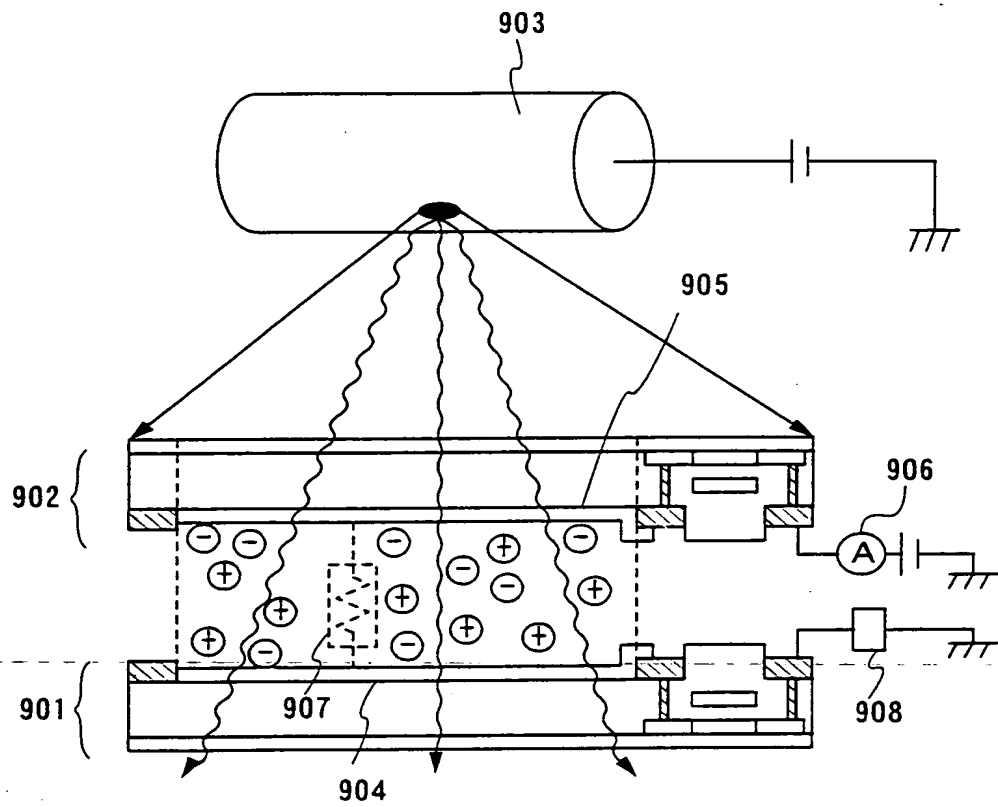


Fig. 9

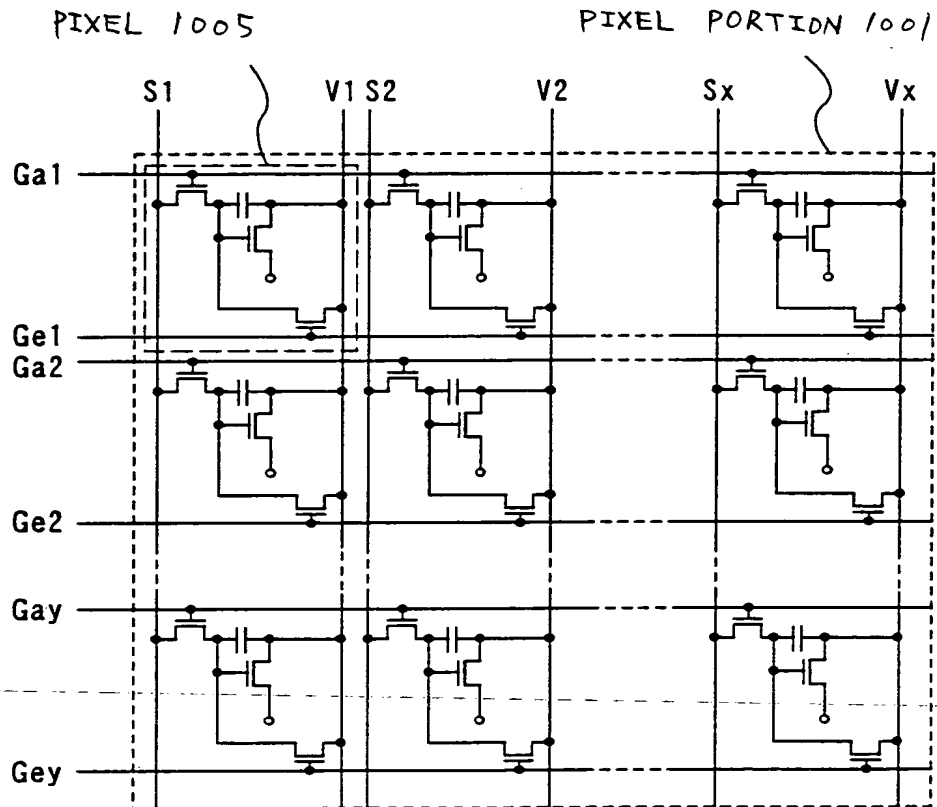


Fig. 10

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SOURCE OF ELECTROMAGNETIC  
WAVES 1101

POWER SOURCE 1104

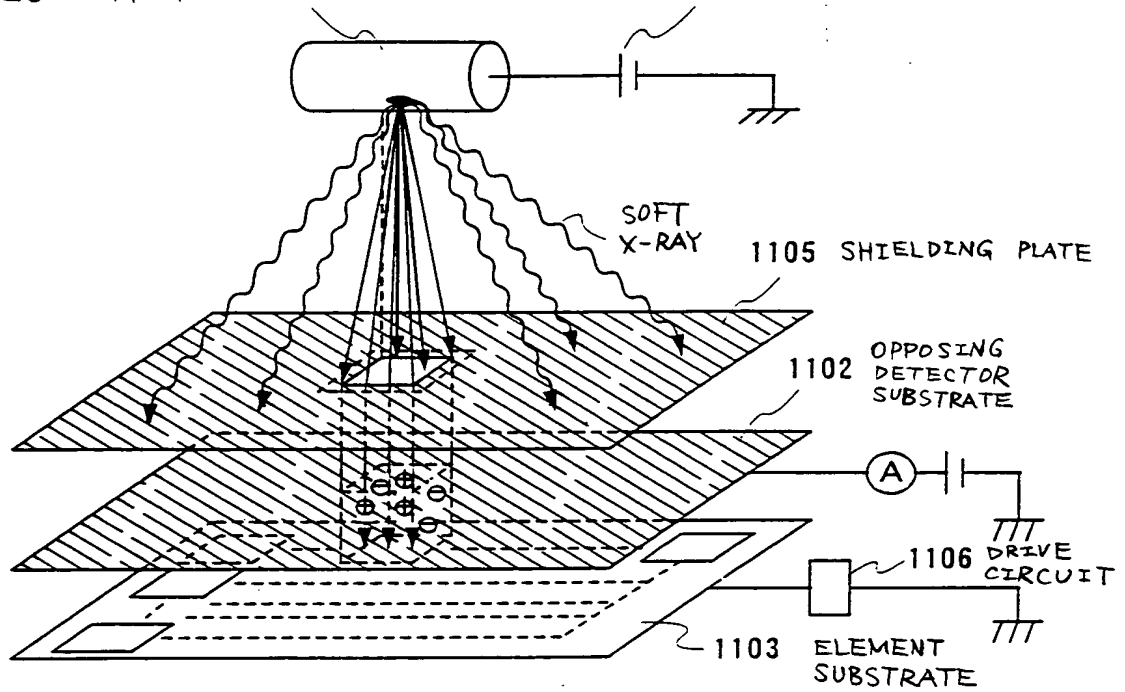


Fig. 11

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SOURCE OF ELECTROMAGNETIC WAVES

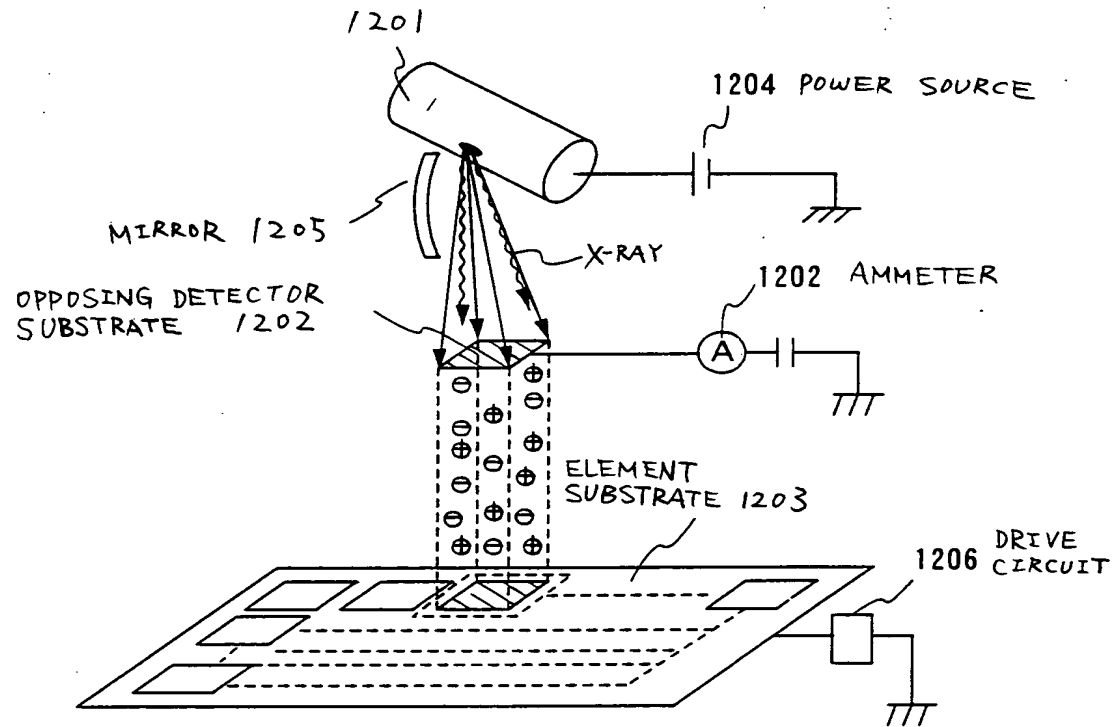


Fig. 12

Fig. 13(A)

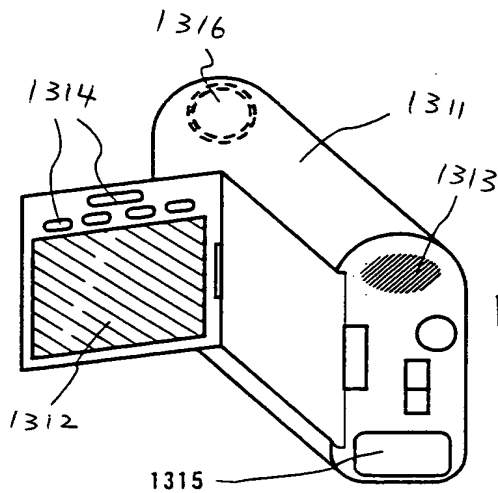
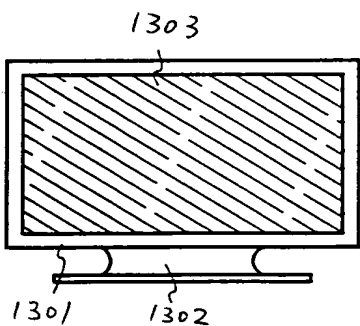


Fig. 13(B)

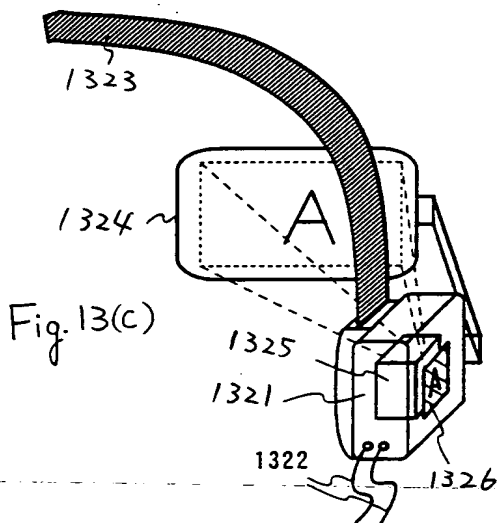


Fig. 13(C)

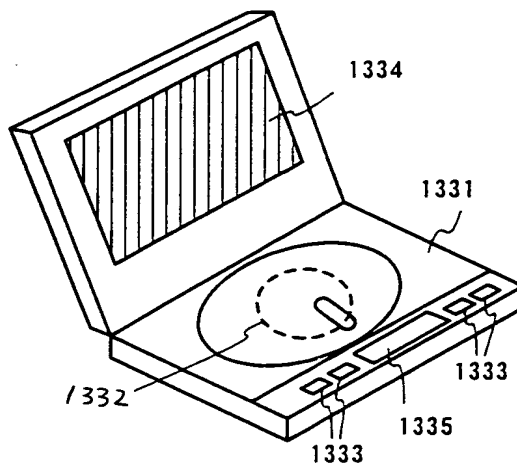


Fig. 13(D)

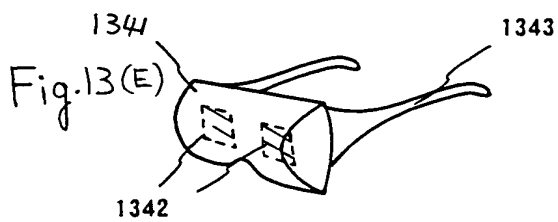


Fig. 13(E)

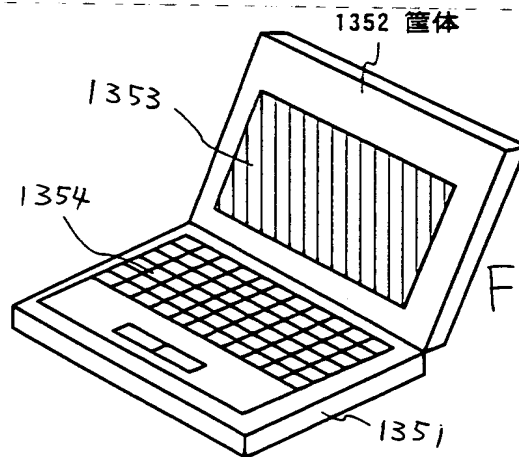


Fig. 13(F)

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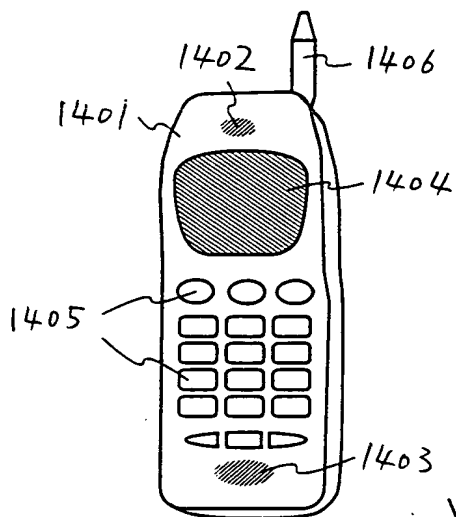


Fig. 14(A)

Fig. 14(B)

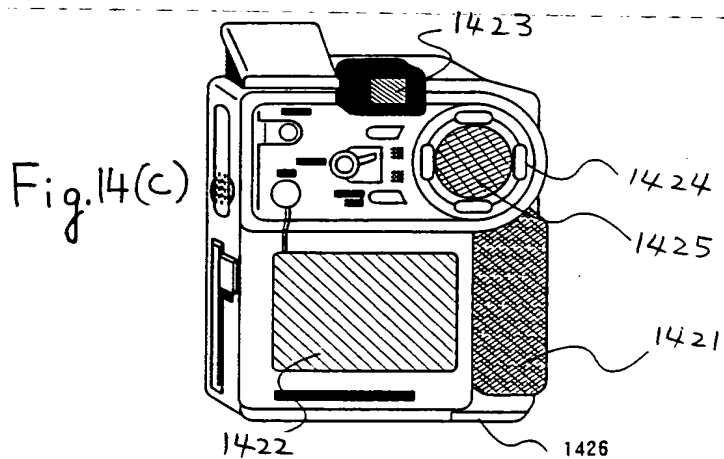
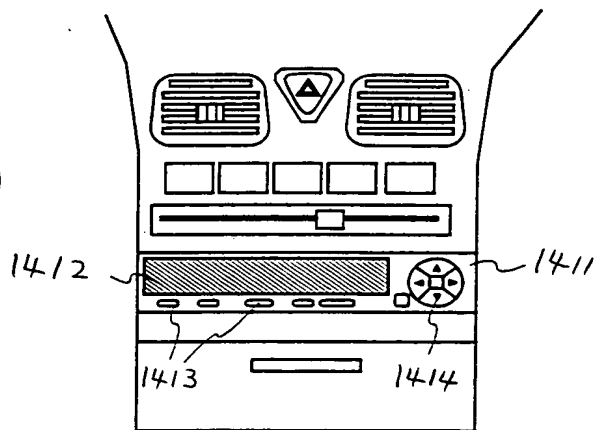
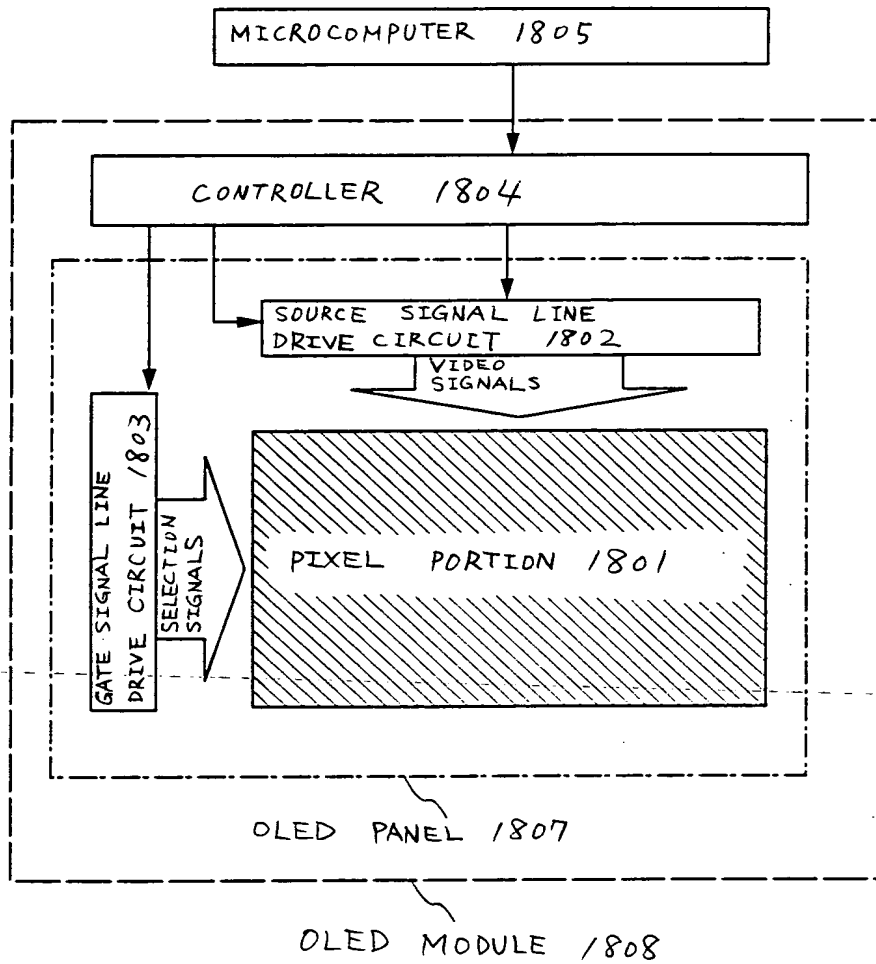


Fig. 15



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Fig. 16(A)

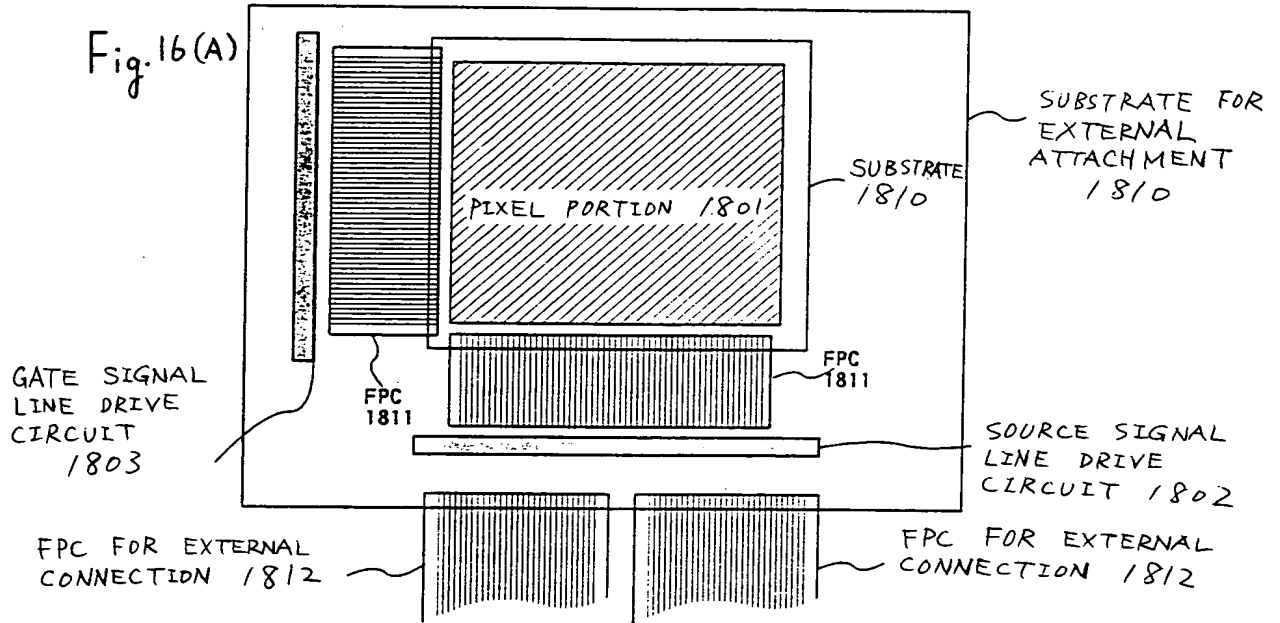


Fig. 16(B)

